Emerging Technologies and Moore's Law: Prospects for the Future

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Economics, Technology, & Innovation

"No exponential is forever ... but we can delay 'forever'."

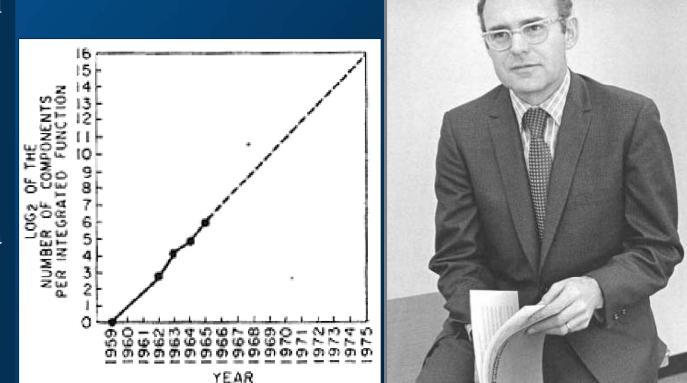
Technologies on Deck

Opportunities for Future Products

Visible Horizon and Beyond

Moore's Law - 1965

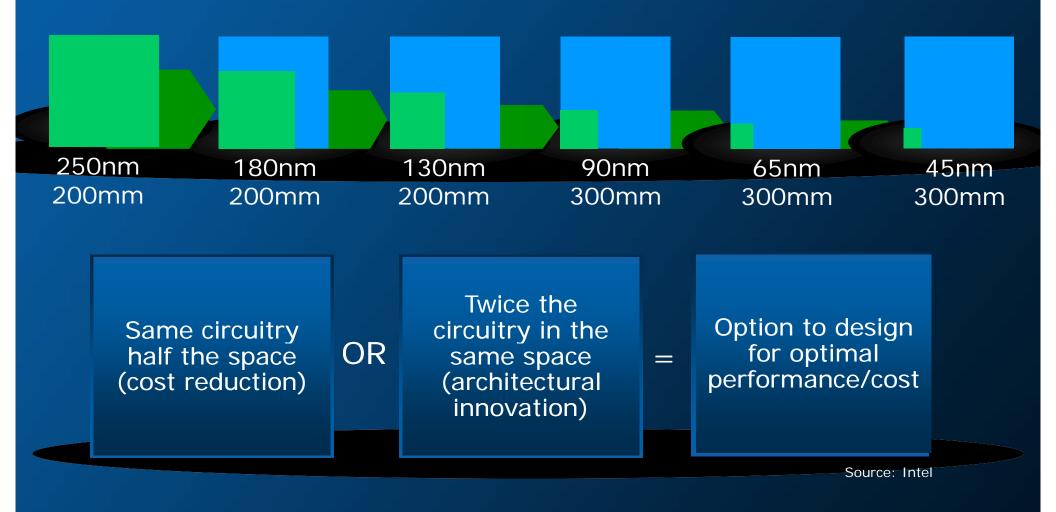
"<u>Reduced cost</u> is one of the big attractions of integrated electronics, and the cost advantage continues to increase as the technology evolves toward the production of larger and larger circuit functions on a single semiconductor substrate." Electronics, Volume 38, Number 8, April 19, 1965



Integrated circuits = Parallel fabrication

Parallel fabrication = Lower cost per function

Enabling Innovation and Cost Reductions

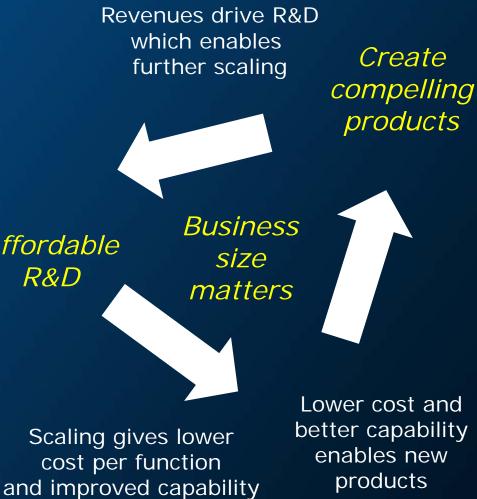


Key Economics: Scaling is Better under almost all circumstances

If you can scale then you should

- Compelling products command higher prices
- Leading technology delivers lower costs
- Enables necessary investment Affordable in R&D
 Affordable R&D

If you can't scale then hope your competitors can't either



Ability to make it work

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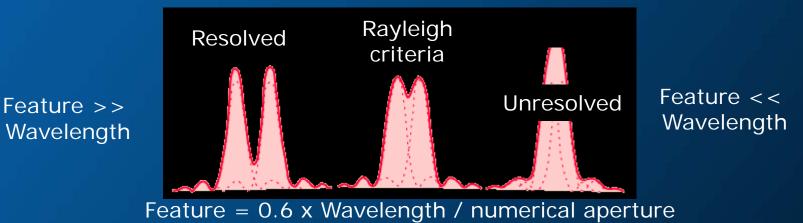
"No exponential is forever ... but we can delay 'forever'."

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"We're limited by the wavelength of light"

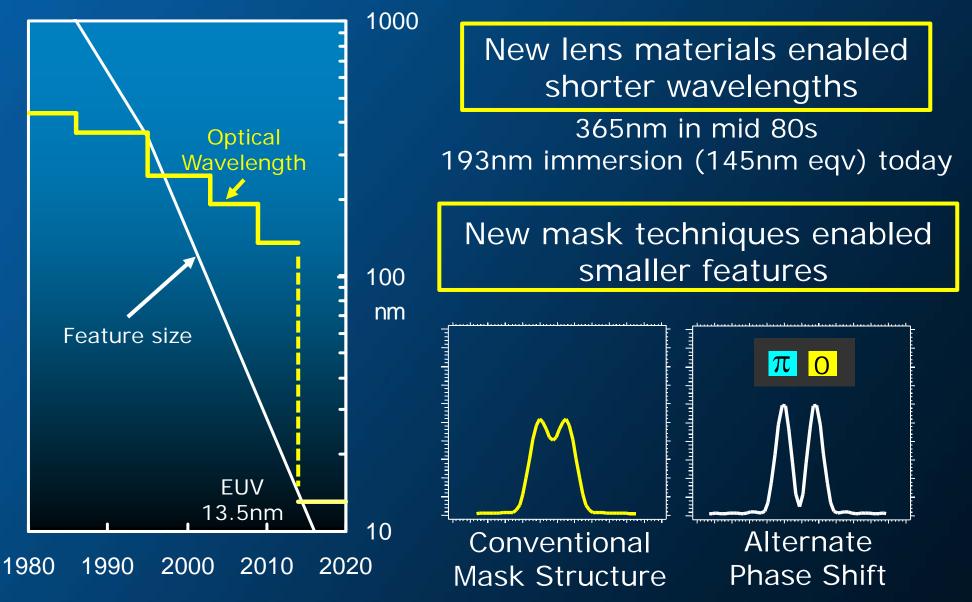


In the limit, microscope objectives with 0.95 N.A. are available and, provided very small fields $(200\mu \times 200\mu)$ are adequate, linewidths < 0.4μ should be achievable under carefully controlled laboratory conditions, and in very thin resist layers.

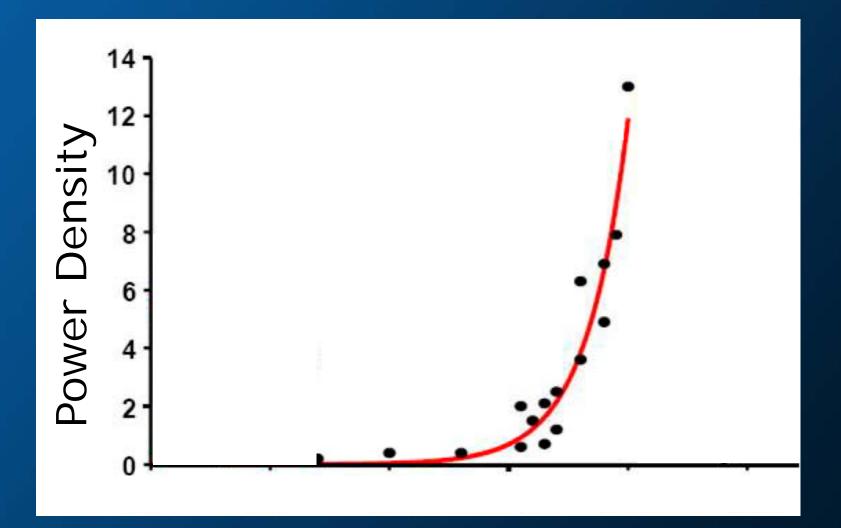
Depth of field will be reduced to about $\pm 0.2\mu$. Deep U.V. ($\lambda = 200$ nm -260 nm) lenses will be difficult to build because of the lack of materials that are transparent at these wavelengths and yet have relatively high refractive indices.

Lithography Scaling Limitations From Broers [1] IEDM Plenary Session 1980

Breaking through the Wall



"We're hitting the power wall"



Source: IBM 2004

Energy per Transistor Continues to Drop



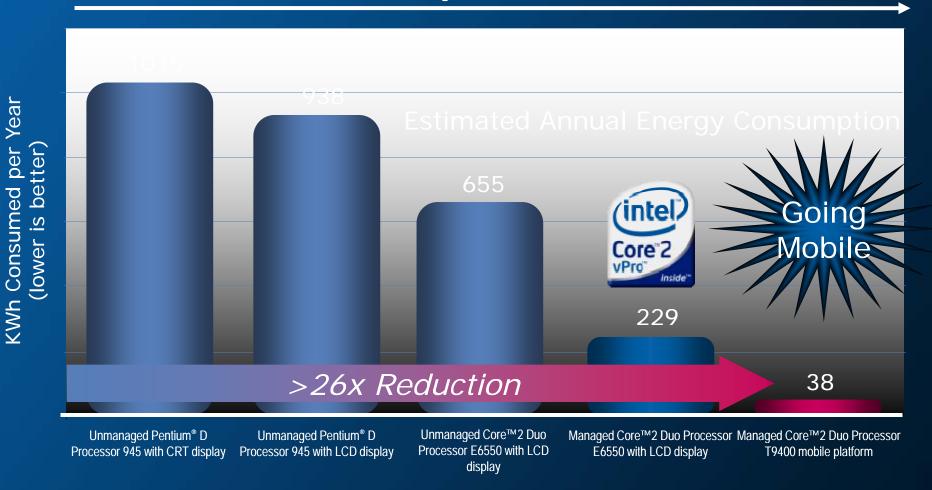
Source: WSTS/Dataquest/Intel

~ 1 Million Factor Reduction In Energy/Transistor Over 30+ Years

10

Energy Consumption is about System Optimization

5 years

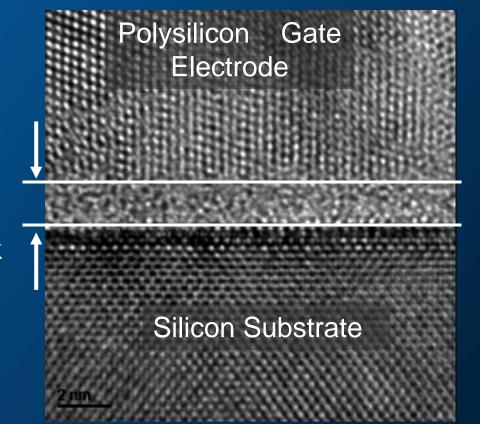


Energy savings comes from combination of transistor scaling and architectural innovations

Performance tests/ratings are provided assuming specific computer systems and/or components and reflect the approximate performance of Intel products as measured by those tests. Any difference in system hardware or software design or configuration may affect actual performance. This data may vary from other material generated for specific marketing requests.

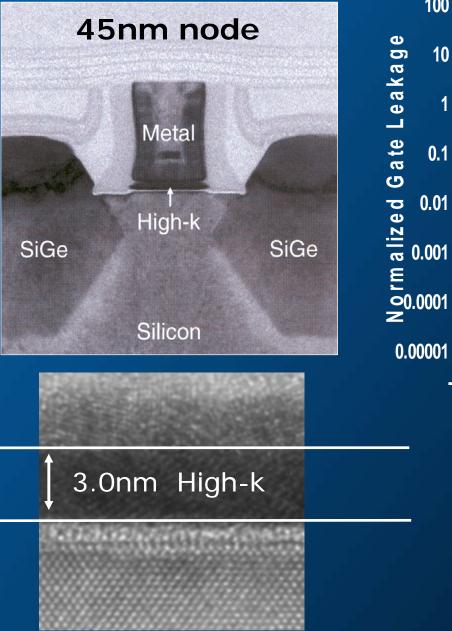
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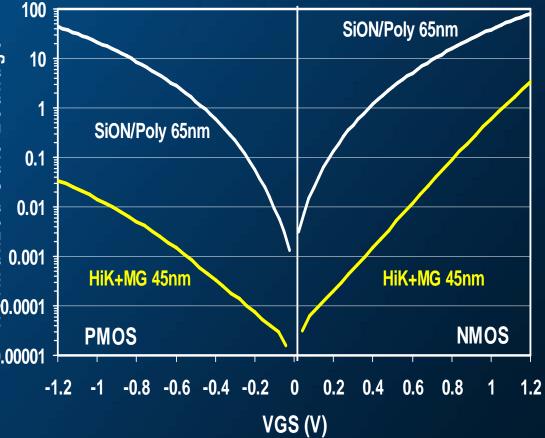
"We're running out of atoms"



1.2 nm SiO₂3-4 atoms thick

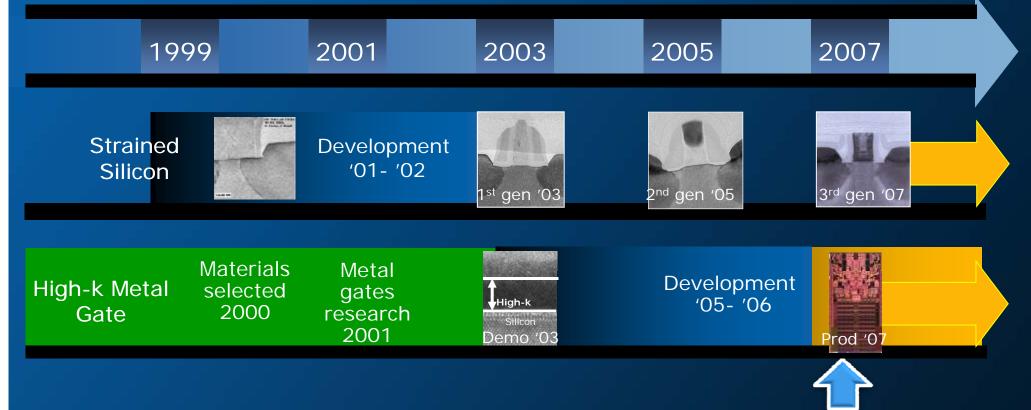
New Materials and New Fabrication





45 nm HK+MG provides >25x gate leakage reduction

The Timing of Research Is Not Always Predictable But a Commitment to Research is Required



Intel 45nm High-k Metal Gate

Ten Years, Millions of Hours Dead Ends, Failures Unwavering Focus

Meanwhile despite these worries Innovations continued on product side

- Personal computing replacing shared computers
- Portable computing
- Connected computers, sharing data, Internet
- Wireless connectivity
- Smaller form factors, pocket computers
- Special purpose devices



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"No exponential is forever ... but we can delay 'forever'."

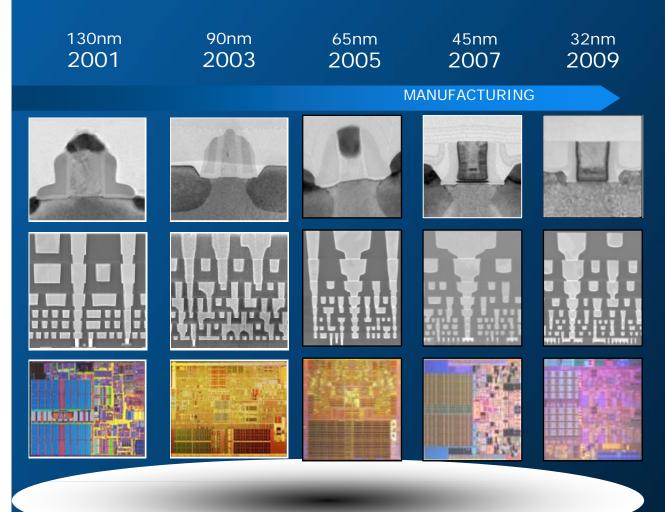
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Opportunities for Future Products

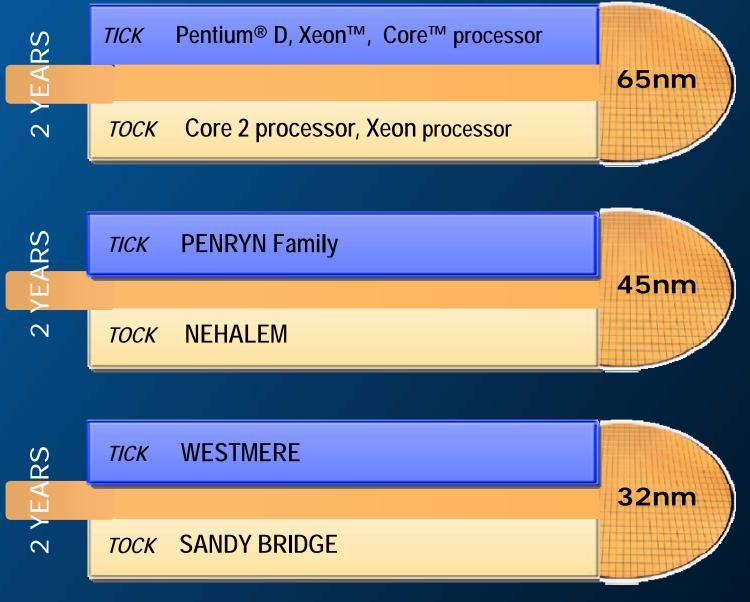
Visible Horizon and Beyond

Steady Technology Cadence

TECHNOLOGY GENERATION



Product Cadence for Sustained Leadership



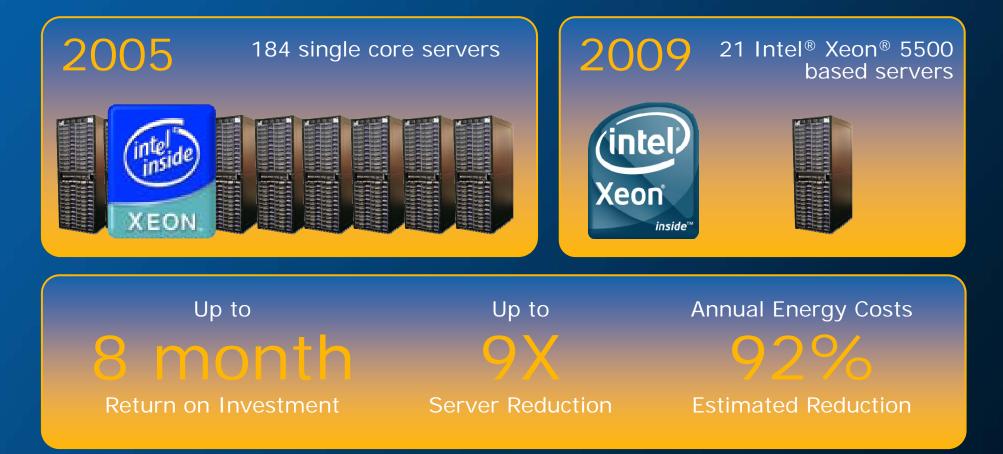
All product information and dates are preliminary and subject to change without notice

So What ?

Generational benefits don't just add,

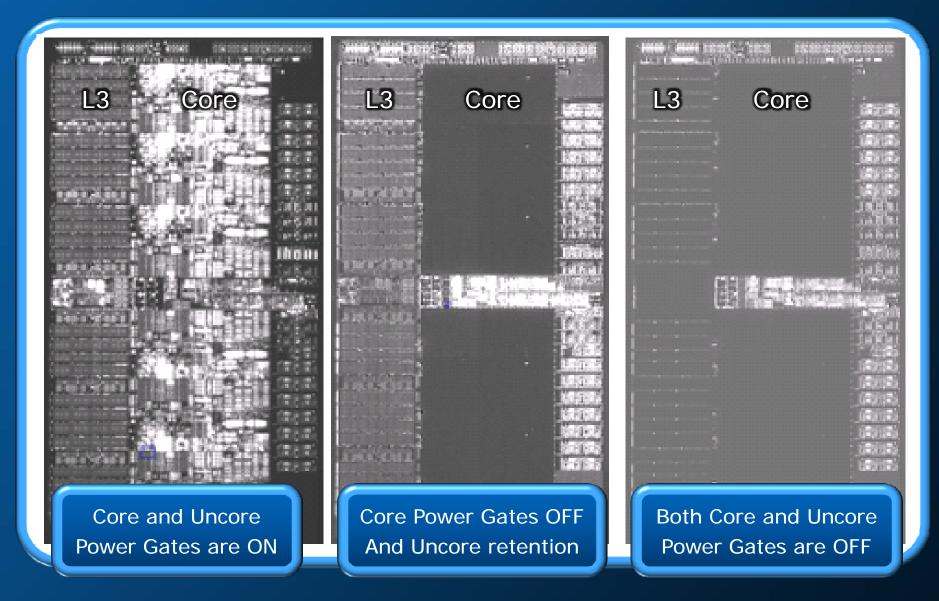
they multiply

Energy Efficiency Improvement (Same Performance Footprint)



Source: Intel estimates as of Nov 2008. Performance comparison using SPECjbb2005 bops (business operations per second). Results have been estimated based on internal Intel analysis and are provided for informational purposes only. Any difference in system hardware or software design or configuration may affect actual performance. For detailed calculations, configurations and assumptions refer to the legal information slide in backup.

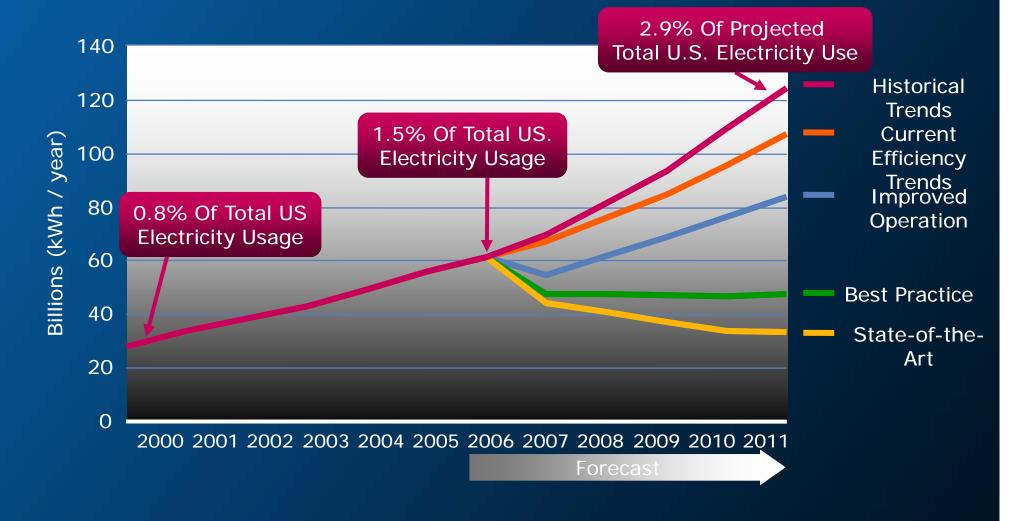
New Fabrication enables New Product Opportunities



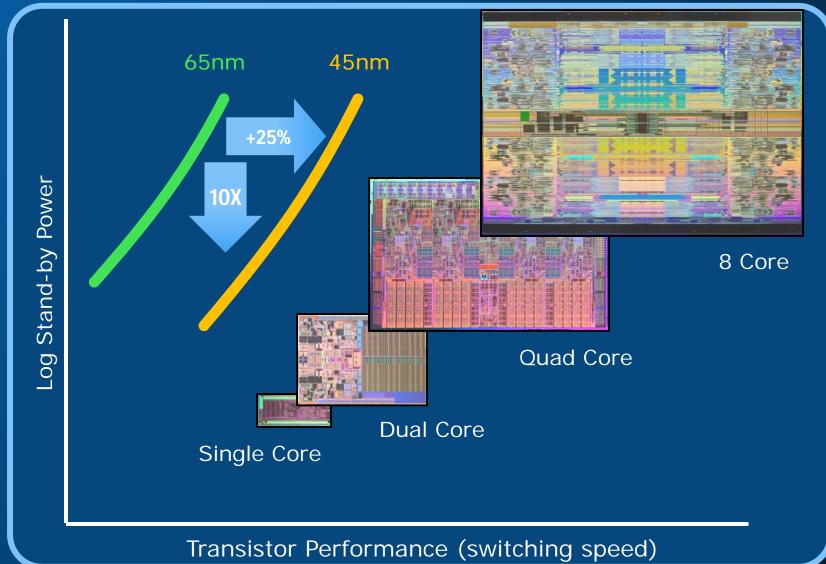
Westmere 6 cores, Infrared imaging showing advanced power management

The Opportunity for Data Center Efficiency

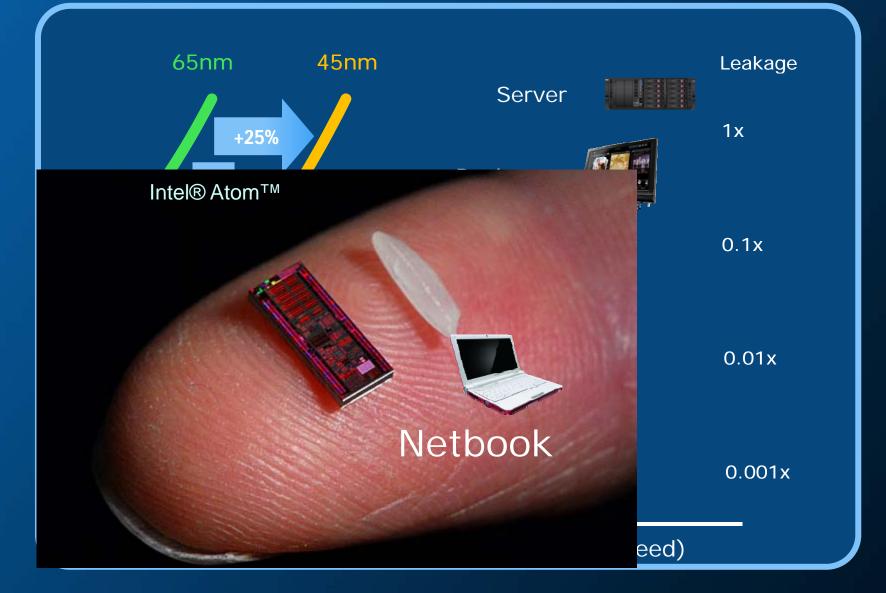
Projected Data Center Energy Use Under Five Scenarios



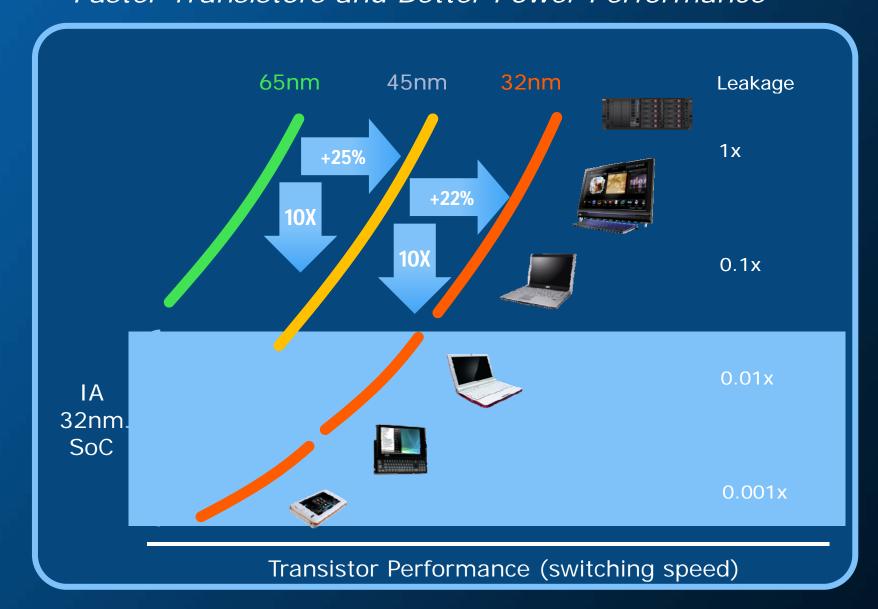
Technology Advances Enable Both Better Products and a Wider Range



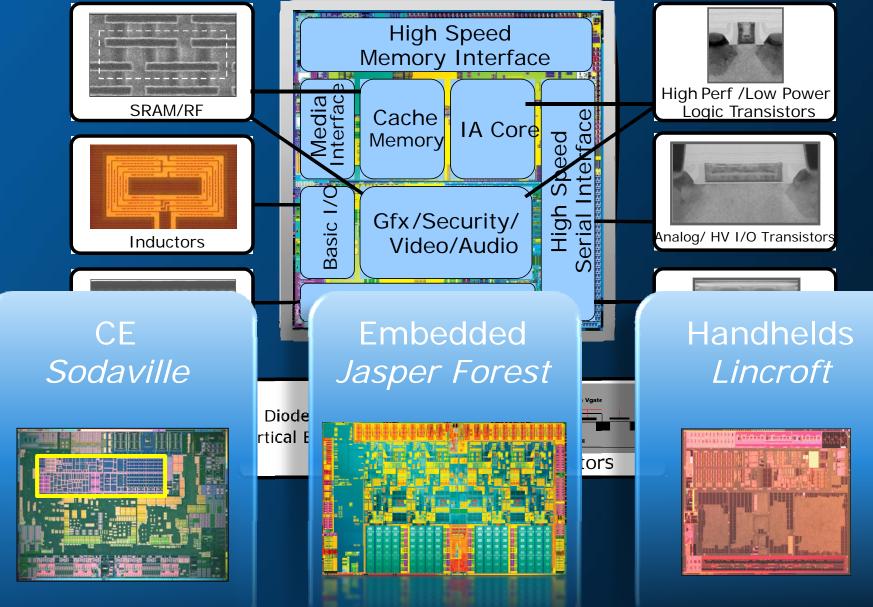
Technology Advances Enable Both Better Products and a Wider Range



Extending Transistor Advantage to SoC's Faster Transistors and Better Power Performance



Implementing a Platform on a Chip



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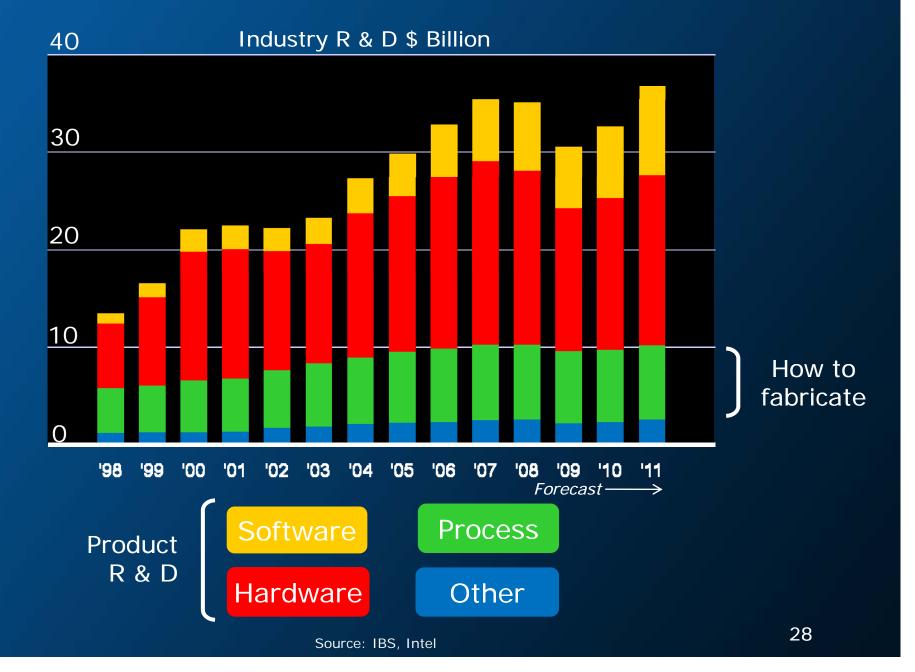
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Industry R & D is Increasing – in dollars and as a percent of revenues



Possible Product Possibilities

- Cloud computing
 - Solving grand challenge problems
 - Enable access anytime anywhere
- Life-like computing
 - Immersive experiences
 - Context aware
- Heterogenous networks
 - Computing in network
 - Integration with bio and sensors

Potential Energy Savings Outside of Information and Communications Technology

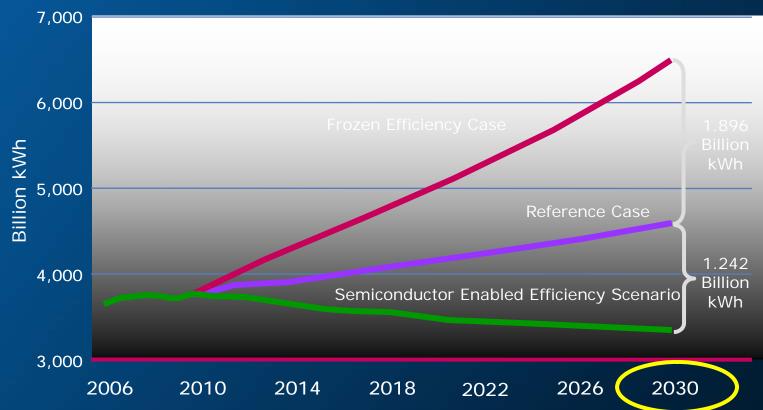
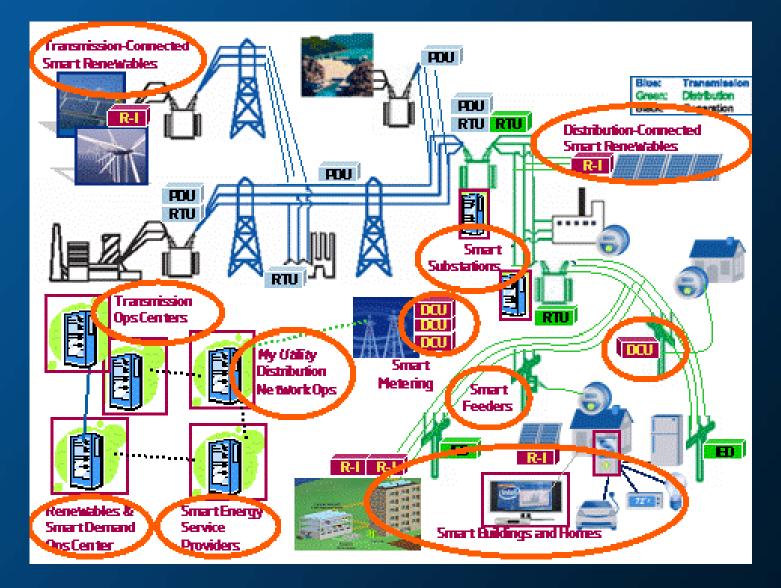


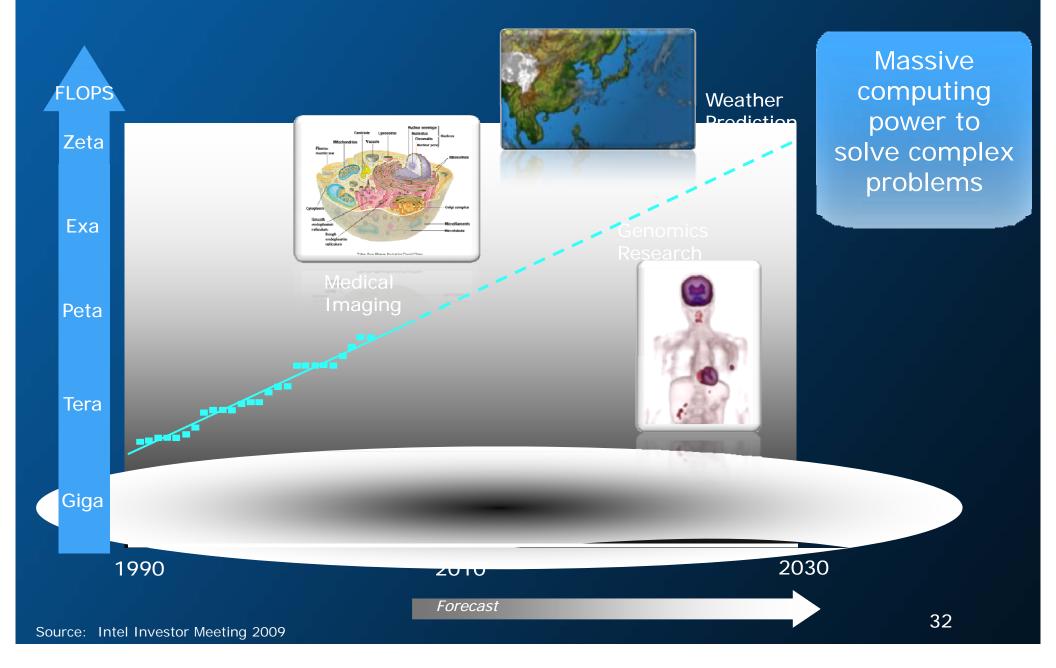
Figure ES-1. Future Electricity Scenarios for the U.S.

Source: ACEEE Report Number E094, May 2009 Semiconductor Technologies: The Potential to Revolutionize U.S. Energy Productivity

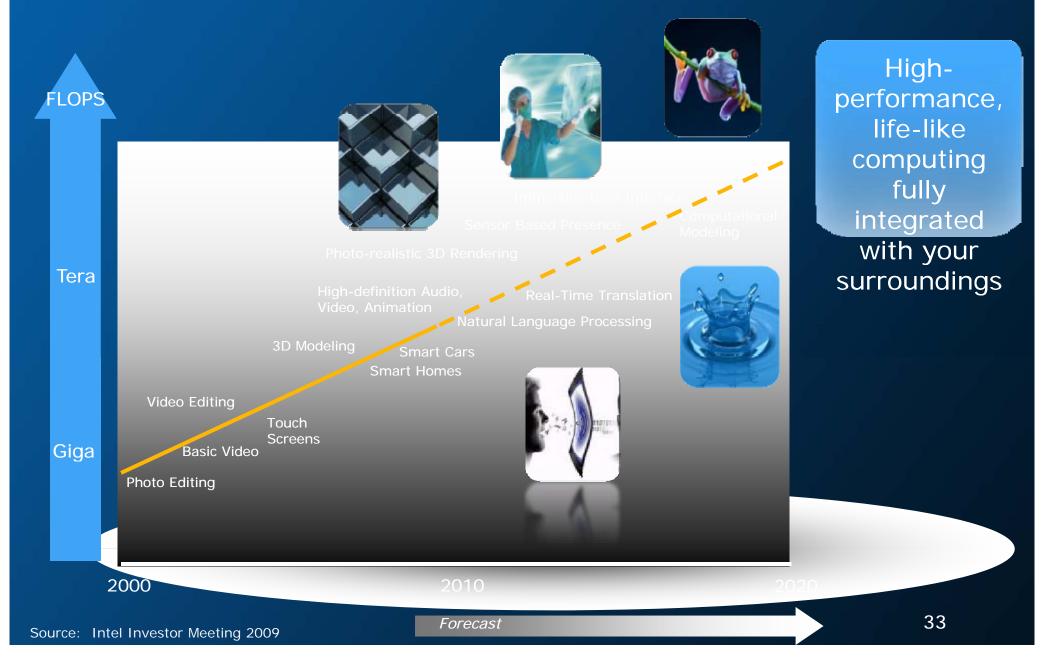
A truly Smart Grid Requires that Microprocessor intelligence be added throughout the network



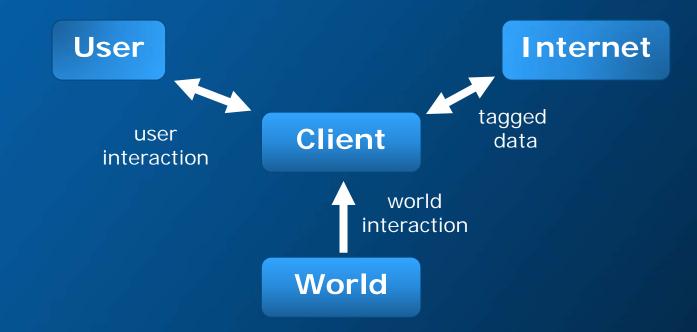
High Performance Computing Segment Needs Decades of Performance Increases



Core Computing Segment Will Need to Increase Performance to Support New Usages

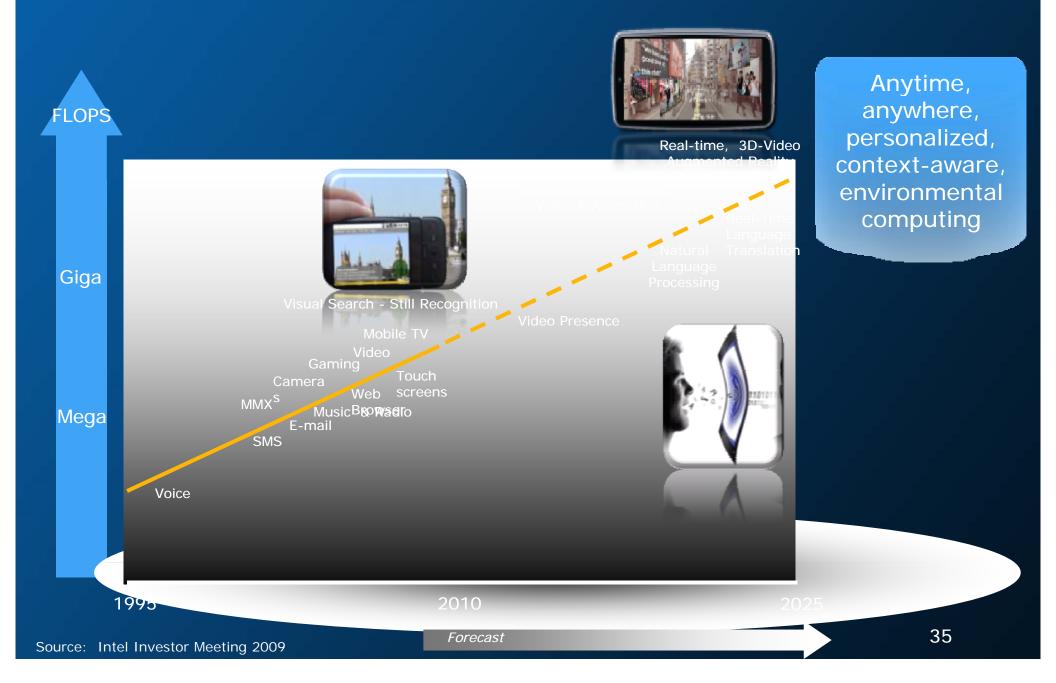


Perceiving the User to Make Interfaces Better



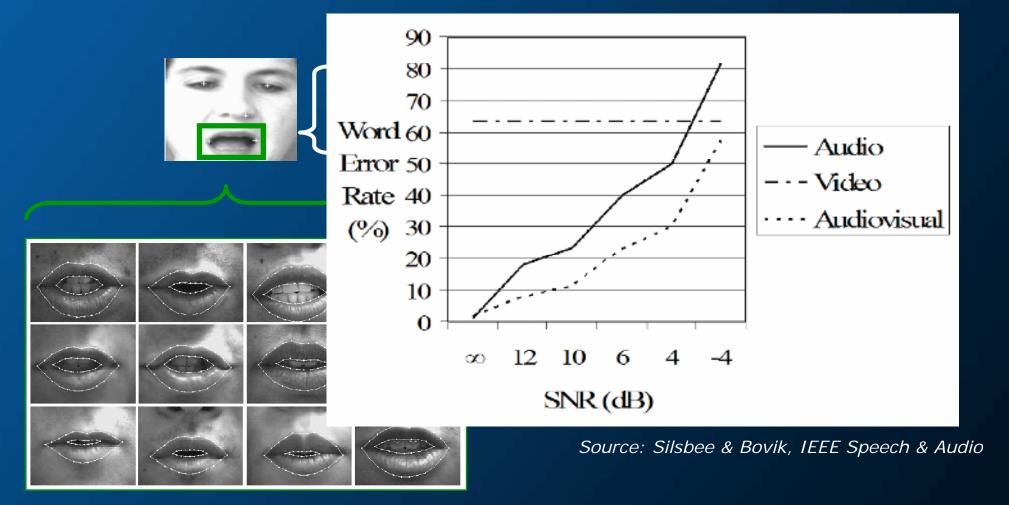


Small Computing Segment Needs More and More Performance At Low Power



Speech Interfaces made Better with Audio-Visual Fusion

Speech recognition works, but fails in noisy environments (mobile)



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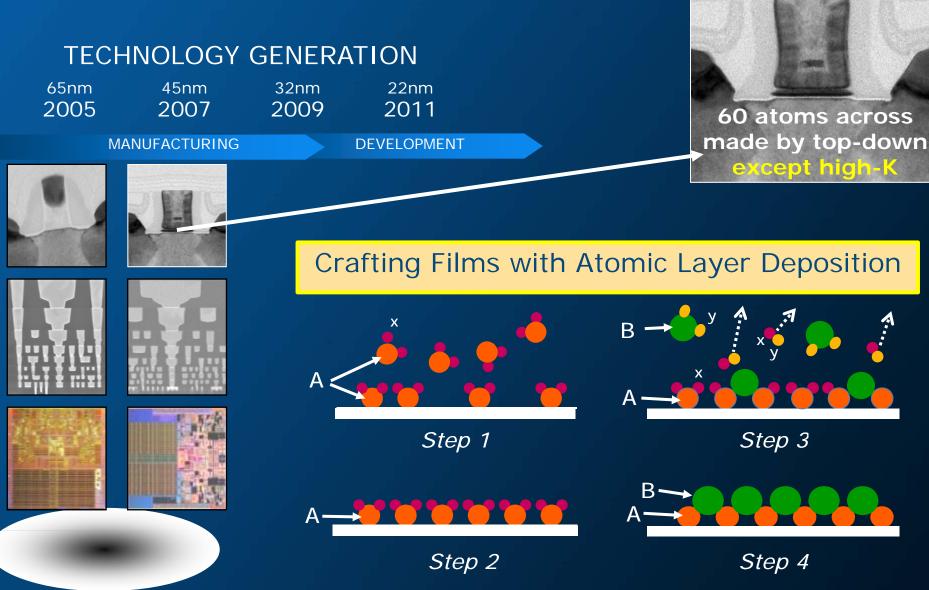
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"We're running out of atoms" Take 2



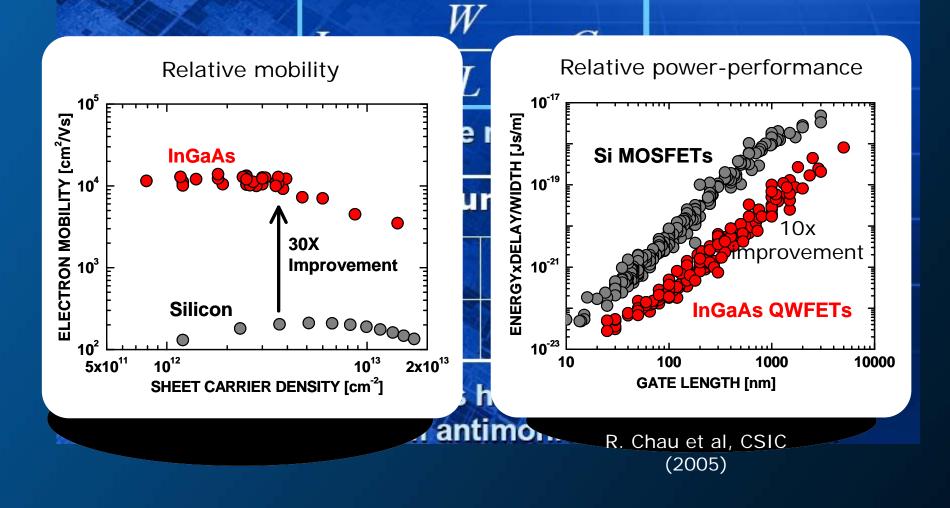
45nm node

New Materials: Enabling the Future of Silicon Technology

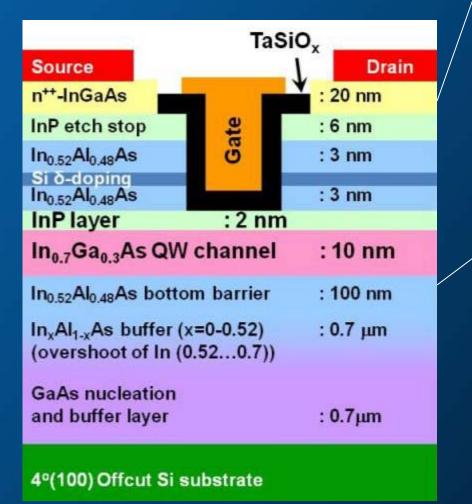
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III-V Materials have Higher Mobility

Increased mobility in the transistor channel leads to higher performance and less energy consumption



Fabrication of QWFET with High-K



InP etch stop

In_{0.53}Ga_{0.47}As cap

In_{0.52}Al_{0.48}As spacer/barrier InP barrier layer

In_{0.7}Ga_{0.3}As QW

10nm

In_{0.52}Al_{0.48}As bottom barrier

Fabrication challenges

- Addition of two more unique materials to the stack (7 total)
- Molecular Beam Epitaxy & Atomic Layer Deposition used
- Atomic deposition precision needed across five critical layers

in partnership with IQE

Designing Materials with Smooth Grains

Polymer

Polydisperse

-

Distribution of
functionality

-

Mw ~ 5k-25k

-

Distribution of free
volume

Monodisperse

-

Monodisperse

-

Monodisperse

-

Monodisperse

-

-

Monodisperse

-

Monodispe

Source: A. De Silva, et al. Adv. Mater. 2008

Polymer Blend + Mature materials platform - Larger individual components

Molecular glass

+ Higher sensitivity at same resolution

- Lower mechanical strength (currently)

Need to engineer materials with components below 1nm

MG

Our limit to visibility goes out ~10 years

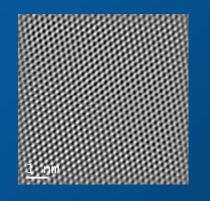
TECHNOLOGY GENERATION

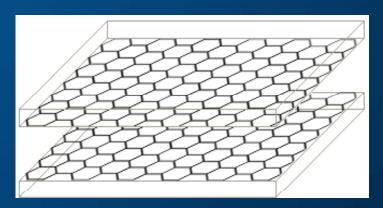


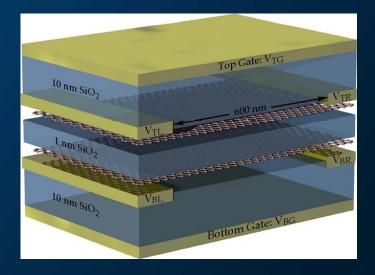
 Silicon lattice is ~ 0.5nm, hard to imagine good devices smaller than 10 lattices across – reached in 2020

Beyond 2020 and possible futures

- Conventional fabrication architectures continue
 - Individual steps continue as 2D layers
 - More and more layers stacked to give increasing function







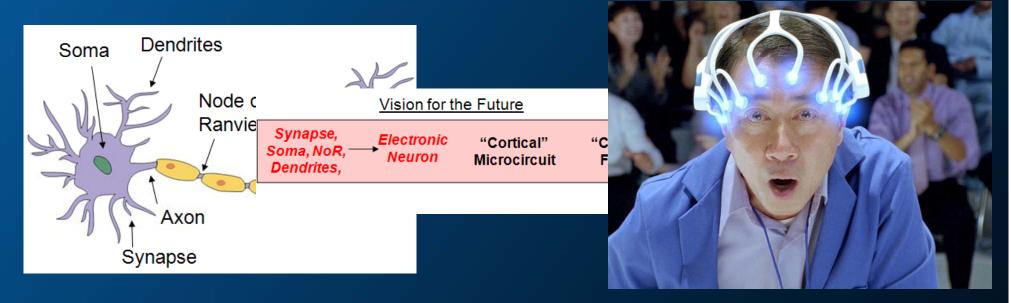
High resolution TEM of graphene Graphene layers can couple together and create a quantum condensate

Bilayer graphene structure Theoretically >10000x less power

Source: M. Gilbert et.al J Comput Electron (2009)

Beyond 2020 and possible futures

- Conventional fabrication architectures continue
 - Individual steps continue as 2D layers
 - More and more layers stacked to give increasing function
- Increasing use of heterogeneous technologies and novel ways to combine technologies
 - Electronics fabricated conventionally but combined with bio interface grown bottoms-up
 - Eliminating, reducing cost of interfaces



Source: NRI, SWAN review 2009

Beyond 2020 and possible futures

- Conventional fabrication architectures continue
 - Individual steps continue as 2D layers
 - More and more layers stacked to give increasing function
- Increasing use of heterogeneous technologies and novel ways to combine technologies
 - Electronics fabricated conventionally but combined with bio interface grown bottoms-up
 - Eliminating, reducing cost of interfaces
- Non-binary or alternate state computation
 - Same fabrication complexity, more value per function

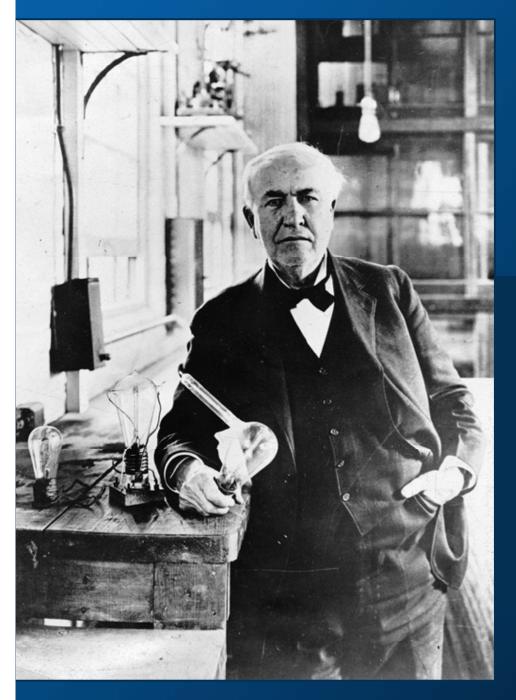
Conclusions

 Moore's Law is not a law of nature, it is an expectation of continued innovation

 We expect to continue through focused research, rapid development, investment in production

 Scaling research is increasingly about materials research, solving problems brings opportunities

 New product opportunities will arise from continued advances in integration, connectivity



Closing Thought

Thomas Edison: Opportunity is missed by most people because it is dressed in overalls and looks like work.

Thank You